

09/681,894

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	500	438/795	USPAT; EPO; JPO	2001/12/02 10:36
2	BRS	L2	487	radiation adj hardening	USPAT; EPO; JPO	2001/12/02 10:37
3	BRS	L3	410879	silicon	USPAT; EPO; JPO	2001/12/02 10:37
4	BRS	L4	626594	semiconductor	USPAT; EPO; JPO	2001/12/02 10:37
5	BRS	L5	4402	microcircuit	USPAT; EPO; JPO	2001/12/02 10:37
6	BRS	L6	3764	vacuum adj furnace	USPAT; EPO; JPO	2001/12/02 10:37
7	BRS	L7	73757	annealing	USPAT; EPO; JPO	2001/12/02 10:38
8	BRS	L8	524238	hydrogen	USPAT; EPO; JPO	2001/12/02 10:38
9	BRS	L9	5407	deuterium	USPAT; EPO; JPO	2001/12/02 10:38
10	BRS	L10	873017	heating	USPAT; EPO; JPO	2001/12/02 10:38
11	BRS	L11	35701	MOSFET	USPAT; EPO; JPO	2001/12/02 10:38
12	BRS	L12	25934	EEPROM	USPAT; EPO; JPO	2001/12/02 10:38

	Type	L #	Hits	Search Text	DBs	Time Stamp
13	BRS	L13	23284	passivation	USPAT; EPO; JPO	2001/12/02 10:39
14	BRS	L14	0	1 and 2	USPAT; EPO; JPO	2001/12/02 10:40
15	BRS	L15	✓	2 and 3 and 4 and 5	USPAT; EPO; JPO	2001/12/02 10:40
16	BRS	L16	405	6 and 7	USPAT; EPO; JPO	2001/12/02 10:40
17	BRS	L17	3615	8 and 9	USPAT; EPO; JPO	2001/12/02 10:40
18	BRS	L18	327	6 and 7 and 10	USPAT; EPO; JPO	2001/12/02 10:40
19	BRS	L19	✓12	6 and 7 and 10 and 13	USPAT; EPO; JPO	2001/12/02 10:41
20	BRS	L20	1441	11 and 12	USPAT; EPO; JPO	2001/12/02 10:41
21	BRS	L21	✓7	8 and 9 and 11 and 12	USPAT; EPO; JPO	2001/12/02 10:41

L15

-4,735,917
*6,261,508
-5,067,985
-4,184,896
-3,954,522

L12

5,891,584
5,805,973
-5,582,610 X 154
*4,200,472

L21

-6,159,829
-6,140,157
-5,830,575